

## SUPPLEMENTARY MATERIAL

# Degradation of Methylparaben Using Optimal WO<sub>3</sub> Nanostructures: Influence of the Annealing Conditions and Complexing Agent

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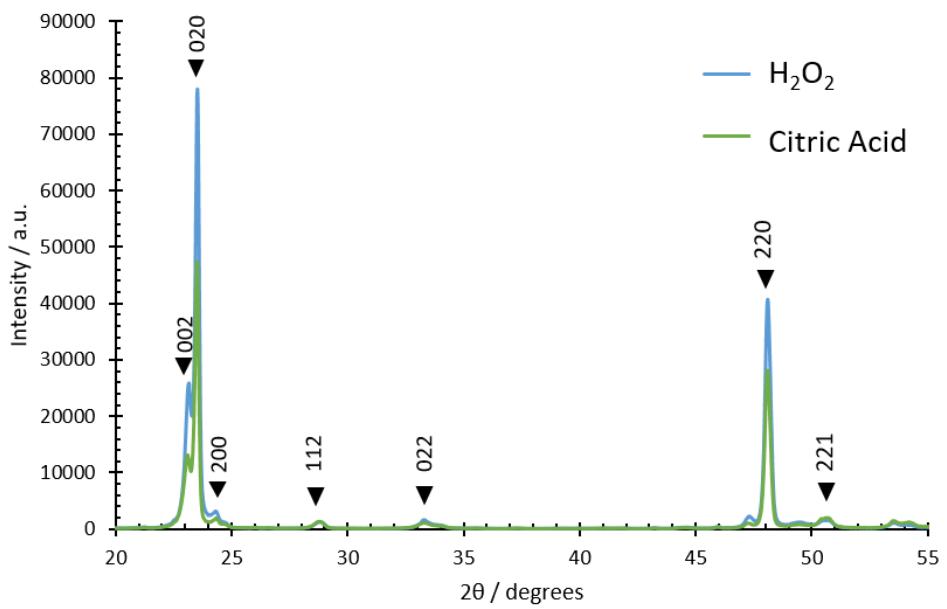
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**Table S1.** Resistance values of the WO<sub>3</sub> samples with different electrolyte and annealing temperatures.

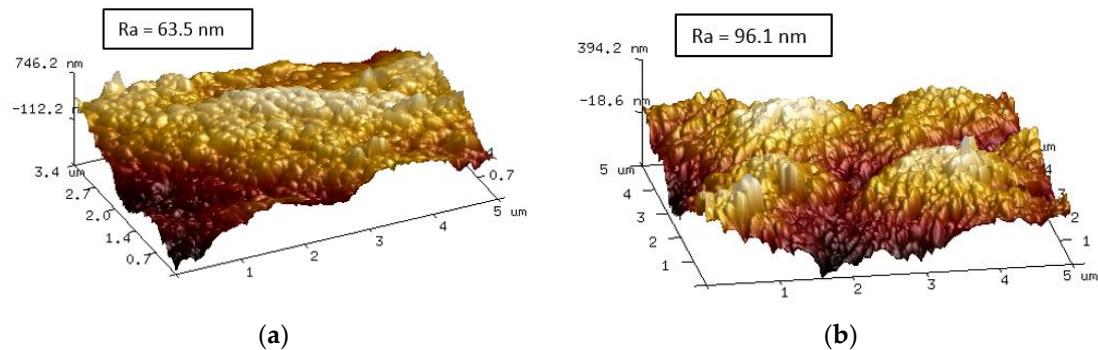
Complexing Agent	Annealing Temperature / °C	R <sub>s</sub> / Ω·cm <sup>2</sup>	R <sub>1</sub> / Ω·cm <sup>2</sup>	R <sub>2</sub> / Ω·cm <sup>2</sup>
H <sub>2</sub> O <sub>2</sub> [49]	400	29 ± 3	159 ± 11	11.8 ± 1.6
	500	44 ± 9	107 ± 26	7.6 ± 1.3
	600	28 ± 6	26 ± 7	3.0 ± 0.9
Citric Acid	400	20±3	43±9	20.1±2.0
	500	17±2	5±1	5.3±1.4
	600	6±1	1±0.9	2.1±0.8

**Table S2.** Density of donors (N<sub>D</sub>) and flat band potential (E<sub>FB</sub>) of the different samples.

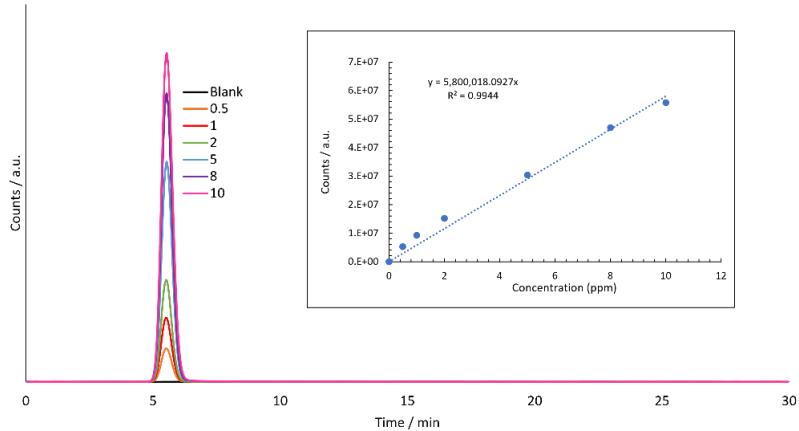
Complexing Agent	Annealing Temperature / °C	N <sub>D</sub> · 10 <sup>19</sup> / cm <sup>3</sup>	E <sub>FB</sub> / V
H <sub>2</sub> O <sub>2</sub> [49]	400	0.4	0.320
	500	1.5	0.326
	600	28.5	0.312
Citric Acid	400	2.0	0.227
	500	9.4	0.305
	600	33.3	0.309



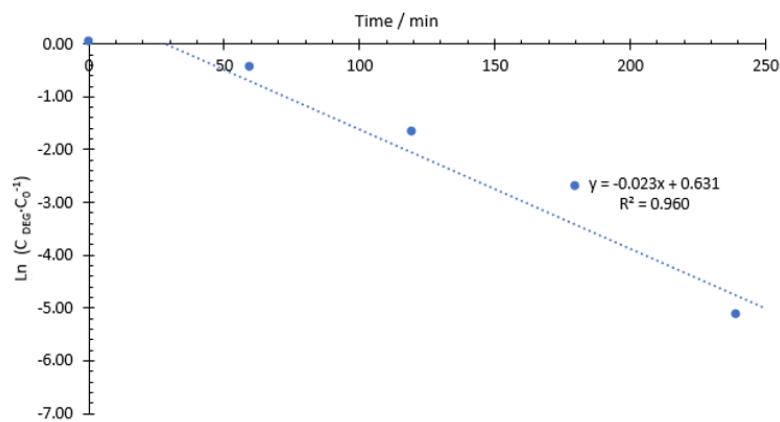
**Figure S1.** XRD plots of the samples anodized with 0.05 M  $\text{H}_2\text{O}_2$  and 0.1M Citric acid at 600 °C.



**Figure S2.** Three-dimension AFM images and roughness value ( $\text{Ra}$ ) of the nanostructures annealed at 600 °C and synthesised with different electrolytes: (a)  $\text{H}_2\text{O}_2$  0.05 M and (b) Citric Acid 0.1 M.



**Figure S3.** EIC at the  $m/z$  value 151.0400 of the standards of MP and inset of the calibration line.

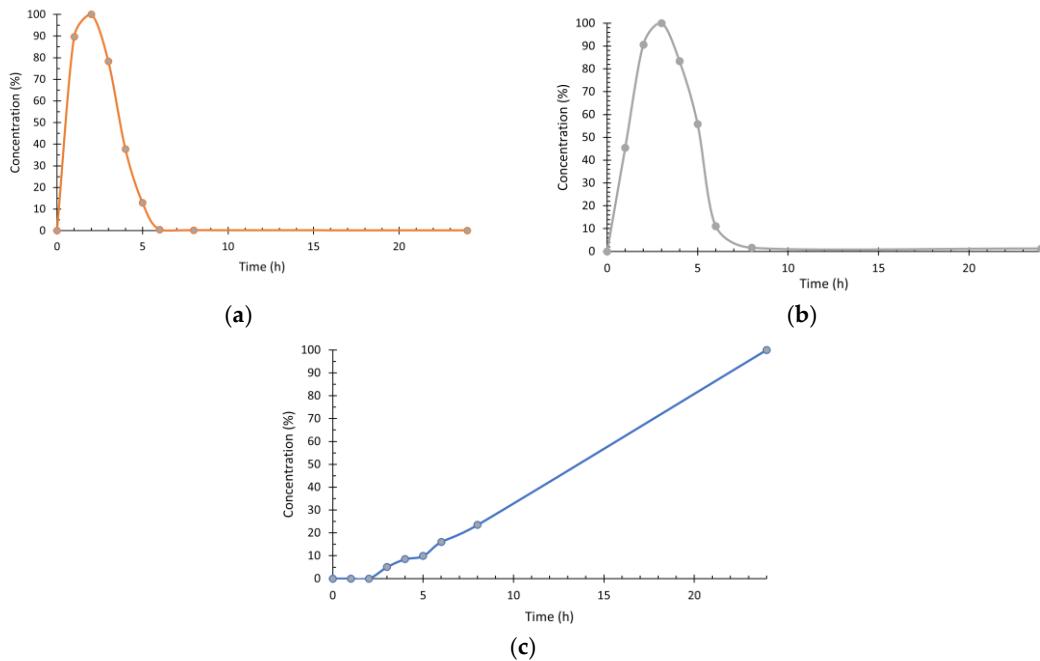


**Figure S4 .** Degradation kinetics of MP.

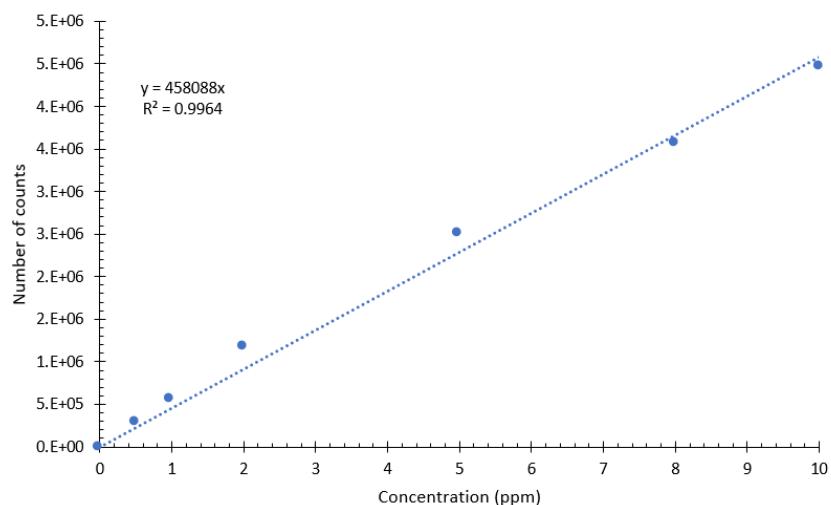
Table S3. Comparison of the kinetic coefficient with literature.

Technique of degradation	Initial concentration of MP (ppm)	K (min <sup>-1</sup> )	References
SPEF (BDD)	45	0.019	[67]
EO (BDD)	100	0.0029	[68]
SPEF	1	75% - 360 min	[69]
SECh (BDD)	100	0.0069	[70]
PC (TiO <sub>2</sub> )	10	100% -240 min	[71]
SECh (BDD)	100	0.024	[72]
PC (TiO <sub>2</sub> )	100	0.018	[73]

Abbreviations: BDD: Boron-doped diamond; EF: Electro-Fenton; EO: Electro-oxidation; PC: Photocatalysis; PEF: Photoelectro-Fenton; SECh: Sonoelectrochemical; SPEF: Solar photoelectro-Fenton.



**Figure S5.** Concentration of all the intermediates in different times during the MP degradation: (a) intermediate A (b) intermediate B (c) intermediateC.



**Figure S6.** Standards of the 4-hydroxybenzoic acid ( $m/z = 136.8914$ ).

**Table S4.** Concentration (ppm) of 4-hydroxybenzoic acid during the degradation of MP.

Time (h)	Area (counts)	Concentration (ppm)
0	0	0
1	0	0
2	0	0
3	60193	0.13
4	117756	0.26
5	101221	0.22
6	191869	0.42
8	279784	0.61
24	1193188	2.60